ABSTRACT

The present disclosure provides semiconductor process equipment and a calibration apparatus thereof, used to calibrate a position of a wafer, the calibration apparatus includes pushing mechanisms and a driving mechanism, a number of the pushing mechanisms is two or more, each of the pushing mechanisms includes an abutment part, and the abutment part is capable of moving from an initial position to a calibration position thereof, and pushing the wafer to move during a movement process, so as to calibrate the position of the wafer; the driving mechanism is connected with the abutment parts of at least two pushing mechanisms, and is configured to drive the abutment parts of the at least two pushing mechanisms to synchronously move between respective initial positions and respective calibration positions. During a calibration process, the driving mechanism operates to simultaneously drive the two or more pushing mechanisms to operate, and further pushes the wafer to move to the calibration position through the abutment part. The two or more abutment parts operate under driving of the same driving mechanism, and a synchronization rate of operation is higher, thereby avoiding position deviation of the wafer caused by asynchronous operation of the pushing mechanisms, improving accuracy of wafer position calibration, and further improving the yield of a process.